

# 中電流離子佈植機 儀器簡介

# Introduction

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- The Varian Ion Implant Systems E500HP Implanters produce charged ions in the source and will extract the ions, analyze them, focus them into a beam, and accelerate them. The ion beam is electrostatically scanned in the X axis and the wafer is mechanically scanned in the Y axis to implant ions uniformly into the wafer.
- The E500HP will implant ions up 200keV. The dose uniformity is consistently better than 0.5%.